

Low-pressure plasma system V80-G

Standard system for cleaning, activation and etching



View into the process chamber.

The system V80-G is suitable for industrial production as well as for R&D applications in the laboratory sector.

The integrated professional SPS control serves as a storage for definable processes and parameters.

System features

- USB port
- Ethernet interface
- Remote maintenance (VPN)
- Microwave coupling from the top
- Swing door

Options

- Vacuum pump
- Ozone trap
- Up to two additional gas inlets
- Aditional excitation frequencies (40 kHz, 13.56 MHz)
- Rotary drum for the treatment of bulk material
- Rotary table
- Pullout door
- Automatic door opening
- Rack with shelves
- Lateral microwave coupling
- Soft start and slow vent

Technical data

Dimensions of the system (W x D x H): 670 x 900 x 1,850 mm Dimensions of the chamber (W x D x H): 400 x 460 x 430 mm Plasma excitation frequency: Microwave (2.45 GHz) Microwave power: 100-1,200 W Gas inlets with mass-flow-control: 2 channels Power supply: 230/400 V, 50/60 Hz Power input: 2,2 kVA Vacuum gauge: Pirani

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